Docket No.

248412US99DIV

IN THE UNITED SEPATES PATENT AND TRADEMARK OFFICE

IN RE APPLICATION OF:

Jamal RAMDANI, et al.

SERIAL NO:

10/767,998

GAU:

2815

FILED:

February 2, 2004

EXAMINER: BAUMEISTER

FOR:

SEMICONDUCTOR STRUCTURE, SEMICONDUCTOR DEVICE, COMMUNICATING DEVICE,

INTEGRATED CIRCUIT, AND PROCESS FOR FABRICATING THE SAME

INFORMATION DISCLOSURE STATEMENT UNDER 37 CFR 1.97

COMMISSIONER FOR PATENTS ALEXANDRIA, VIRGINIA 22313

SIR:

Applicant(s) wish to disclose the following information.

REFERENCES

- The applicant(s) wish to make of record the references listed on the attached form PTO-1449. Copies of the listed references are attached, and copies were submitted in Application Serial No. 09/808,888 according to the attached copy of a Granted Petition. This application contains related subject matter.
- A check or credit card payment form is attached in the amount required under 37 CFR §1.17(p).

RELATED CASES

- Attached is a list of applicant's pending application(s), published application(s) or issued patent(s) which may be related to the present application. In accordance with the waiver of 37 CFR 1.98 dated September 21, 2004, copies of the cited pending applications are not provided. Cited published and/or issued patents, if any, are listed on the attached PTO form 1449.
- A check or credit card payment form is attached in the amount required under 37 CFR §1.17(p).

CERTIFICATION

- ☐ Each item of information contained in this information disclosure statement was first cited in any communication from a foreign patent office in a counterpart foreign application not more than three months prior to the filing of this statement.
- □ No item of information contained in this information disclosure statement was cited in a communication from a foreign patent office in a counterpart foreign application or, to the knowledge of the undersigned, having made reasonable inquiry, was known to any individual designated in 37 CFR §1.56(c) more than three months prior to the filing of this statement.

DEPOSIT ACCOUNT

Please charge any additional fees for the papers being filed herewith and for which no check or credit card payment is enclosed herewith, or credit any overpayment to deposit account number <u>15-0030</u>. A duplicate copy of this sheet is enclosed.

10/26/2004 EAREGAY1 00000047 10767998

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Customer Number

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Tel. (703) 413-3000 Fax. (703) 413-2220 (OSMMN 05/03) Respectfully submitted

OBLON, SPIVAK, McCLELLAND, MAIER & NEUSTADT, P.C.

Richard L. Treanor

Registration No. 36,379

OCT 2 5 2004 U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OR ICE ATOY DOCKET NO. SERIAL NO. Form PTO 1449 (Modified) 248412US99DIV 10/767,998 RADEN APPLICANT LIST OF REFERENCES CITED BY APPLICANT Jamal RAMDANI, et al. FILING DATE GROUP February 2, 2004 2815 U.S. PATENT DOCUMENTS DOCUMENT FILING DATE **EXAMINER** DATE NAME CLASS **SUB** IF APPROPRIATE INITIAL NUMBER CLASS AΑ 3,802,967 04/09/74 Ladany et al. AB 4,174,422 11/13/79 Matthews et al. AC 4,404,265 09/13/83 Manasevit ΑD 4,482,906 11/13/84 Hovel et al. Morimoto et al. ΑĘ 4,523,211 06/11/85 AF 4,661,176 04/28/87 Manasevit AG 4,793,872 12/27/88 Meunier et al. 4,846,926 07/11/89 AΗ Kay et al. 08/08/89 Akasaki et al. AJ 4,855,249 4,891,091 01/02/90 Shastry ΑK 4,912,087 03/27/90 Aslam et al. 05/22/90 AL 4,928,154 Umeno et al. 10/16/90 Wanlass et al. ΑМ 4,963,949 ΑN 5,141,894 08/25/92 Bisaro et al. 10/27/92 Calviello et al. ΑO 5.159.413 12/22/92 Connell et al. ΑP 5,173,474 AQ 06/22/93 Chisholm et al. 5,221,367 AR 5,225,031 07/06/93 McKee et al. 10/25/94 Neville Connell et al. AS 5.358.925 5,393,352 02/28/95 Summerfelt ΑТ ΑÜ 5,418,216 05/23/95 Fork ĀΫ 5,450,812 09/19/95 McKee et al. ΑW 5,478,653 12/26/95 Guenzer ΑX 5,482,003 01/09/96 McKee et al. 05/07/96 Nashimoto ΙAΥ 5,514,484 5,556,463 09/17/96 ΑZ Guenzer BA 5,588,995 12/31/96 Sheldon BB 5,670,798 09/23/97 Schetzina 5,733,641 BC 03/31/98 Fork et al. BD 5,735,949 04/07/98 Mantl et al. BE 5,741,724 04/21/98 Ramdani et al. 09/22/98 Yano et al. BF 5,810,923 RG 5,830,270 11/03/98 McKee et al. 06/15/99 Jia ВH 5,912,068 02/01/00 Wollesen ВІ 6,020,222 6,045,626 04/04/00 Yano et al. Northrup et al. вк 6,064,078 05/16/00 05/16/00 Park BL 6,064,092 вм 6,096,584 08/01/00 Ellis-Monaghan et al. ΒN 6,103,008 08/15/00 McKee et al. 10/24/00 во 6,136,666 BP 6,174,755 01/16/01 Manning

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U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE SERIAL NO. ATTY DOCKET NO. Form PTO 1449 (Modified) 10/767,998 248412US99DIV APPLICANT Jamal RAMDANI, et al. LIST OF REFERENCES CITED BY APPLICANT GROUP **FILING DATE** 2815 February 2, 2004 **U.S. PATENT DOCUMENTS** FILING DATE **EXAMINER** DOCUMENT DATE NAME CLASS SUB INITIAL **CLASS** IF APPROPRIATE NUMBER CA 3,766,370 10/16/73 Walther СВ 4,006,989 02/08/77 Andringa CC 4,284,329 08/18/81 Smith et al. CD 4,777,613 10/11/98 Shahan et al. CE 4,802,182 01/31/89 Thornton et al. 4,882,300 11/21/89 Inoue et al. 01/23/90 Suzuki CG4,896,194 03/12/91 СН 4,999,842 Huang et al. CI 5,081,062 01/14/92 Vasudev et al. 5,155,658 10/13/92 nam et al. CK 09/28/93 Ramesh 5,248,564 11/09/93 \overline{CL} 5,260,394 Tazaki et al. 12/14/93 СМ 5,270,298 Ramesh CN 5,286,985 02/15/94 Taddiken 05/10/94 $\overline{\mathsf{co}}$ 5,310,707 Oishi et al. CP 07/05/94 Summerfelt 5,326,721 CQ 5,404,581 04/04/95 Honjo CR 5,418,389 05/23/95 Watanabe 07/25/95 Dijaii et al. CS 5.436.759 11/19/96 Nashimoto CT 5,576,879 02/25/97 Abrokwah, et al. CU 5,606,184 CV 5,640,267 06/17/97 May et al. CW 5.674.366 10/07/97 Hayashi et al. 03/17/98 Chandonnet et al. \overline{CX} 5,729,641 5,790,583 08/04/98 CY Ho 5,825,799 10/20/98 Ho et al. DA 01/05/99 Beranek et al. 5,857,049 02/23/99 Brunel et al. DB 5.874,860 Ho et al. DC 5,926,496 07/20/99 DD 5,937,285 08/10/99 Abrokwah, et al. DE 5,981,400 11/09/99 DF 5,990,495 11/23/99 Ohba 12/14/99 Corman et al. lDG 6.002.375 12/28/99 Nghiem ď 6,008,762 ם 6,055,179 04/25/00 Koganei et al. 6,107,653 08/22/00 Fitzgerald DJ DΚ 09/05/00 Yu et al. 6,113,690 09/05/00 Nghiem DΈ 6,114,996 09/19/00 DM 6,121,642 Newns 10/03/00 DN 6,128,178 Newns DO 11/07/00 McKee et al. 6.143.072 DΡ 02/06/01 6,184,144 Lo 04/24/01 DQ 6,222,654 Frigo

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LIST OF	LIST OF REFERENCES CITED BY APPLICANT			APPLICANT Jamal RAMDANI, et al.				
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EXAMINER		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE	
INITIAL	EA	4,484,332	11/20/84	Hawrylo		CLASS	II AFFICITIALE	
	EB	4,815,084	03/21/89	Scifres et al.		 		
	EC	4,876,219	10/24/89	Eshita et al.	- 			
	ED	4,963,508	10/16/90	Umeno et al.	_	 		
	EE	5,060,031	10/22/91	Abrokwah, et al.		†		
	EF	5,063,166	11/05/91	Mooney et al.	<u> </u>			
	EG	5,116,461	05/26/92	Lebby et al.	1			
	EH	5.127.067	06/30/92	Delcoco et al.				
	ΕI	5,144,409	09/01/92	Ма				
·	EJ	5,293,050	03/08/94	Chapple-Sokol et al				
	EK	5,356,831	10/18/94	Calviello et al.				
	EL	5,391,515	02/21/95	Kao et al.				
	ЕМ	5,442,191	08/15/95	Ма				
	EN	5,444,016	08/22/95	Abrokwah, et al.		1		
	EO	5,480,829	01/02/96	Abrokwah, et al.				
	EP	5,528,414	06/18/96	Oakley				
	EQ	5,614,739	03/25/97	Abrokwah et al.		-		
	ER	5,729,394	03/17/98	Sevier et al.				
	ES	5,731,220	03/24/98	Tsu et al.				
	ET	5,764,676	06/09/98	Paoli et al.				
	EU	5,777,762	07/07/98	Yamamoto				
	EV	5,778,018	07/07/98	Yoshikawa et al.				
	EW	5,778,116	07/07/98	Tomich				
	EX	5,801,105	09/01/98	Yano et al.				
	EY	5,828,080	10/27/98	Yano et al.				
	EZ	5,858,814	01/12/99	Goossen et al.				
<u> </u>	FA	5,861,966	01/19/99	Ortel				
	FB	5,883,996	03/16/99	Knapp et al.				
	FC	5,995,359	11/30/99	Klee et al.				
	FD	6,058,131	05/02/00	Pan				
	FE	6,137,603	10/24/00	Henmi				
	FF	6,146,906	11/14/00	noue et al.				
	FG	6,173,474	01/16/01	Conrad				
	FH	6,180,252	01/30/01	Farrell et al.				
	FI	4,242,595	12/30/0	Lehovec				
	FJ	4,398,342	08/16/83	Pitt et al.	4	ļ		
	FK	4,424,589	01/03/84	Thomas et al.				
	FL	4,876,208	10/24/89	Gustafson et al.				
	FM	4,482,422	11/84	McGinn et al.			<u> </u>	
	FN	4,667,088	05/19/87	Kramer		_	ļ	
	FO	4,772,929	09/20/88	Manchester et al.		1	<u> </u>	
	FP	4,841,775	06/27/89	Ikeda et al.		_	 	
	FQ	4,845,044	07/04/89	Ariyoshi et al.			<u></u>	

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EXAMINER	-	DOCUMENT	DATE	U.S. PATENT DOCUMENTS NAME	CLASS	SUB	FILING DATE
INITIAL		NUMBER			02.00	CLASS	IF APPROPRIATE
	GA	4,868,376	09/19/89	Lessin et al.			
	GB	4,885,376	12/05/89	Verkade			
	GC	4,888,202	12/89	Murakami et al.			
	GD	4,891,091	12/90	Wanlass et al.			
	GE	5,051,790	09/24/91	Hammer			
	GF	5,055,445	10/08/91	Belt et al.			
	GG	5,081,519	11/14/92	Nishimura et al.			
	GH	5,143,854	09/01/92	Pirrung et al.			
	GI	5,185,589	02/09/93	Krishnaswamy et al.			
	GJ	5,191,625	03/02/93	Gustavsson			
	GK	5,194,397	03/16/93	Cook et al.			
	GL	5,208,182	05/04/93	Narayan et al.			
	GМ	5,216,729	06/01/93	Berger et al.			
• A	GN	5,314,547	05/24/94	Heremans et al.			
	GO	5,352,926	10/04/94	Andrews			
	GP	5,356,509	10/18/94	Terranova et al.	į		
	GQ	5,371,734	12/06/94	Fischer			
2. 7	GR	5,372,992	12/94	Itozaki et al.			
	GS	5,405,802	04/11/95	Yamagata et al.			
	GT	5,442,561	08/15/95	Yoshizawa et al.			
-	GU	5,453,727	09/26/95	Shibasaki et al.			
	GV	5,466,631	11/14/95	Ichikawa et al.			
	GW	5,473,047	12/05/95	Shi			
	GX	5,473,171	12/95	Summerfelt			
	GY	5,479,033	12/26/95	Baca et al.			
	GZ	5,486,406	01/23/96	Shi			
	HA	5,491,461	02/13/96	Partin et al.			
	нв	5,492,859	02/20/96	Sakaguchi et al.	j		
	нс	5,494,711	02/27/96	Takeda et al.			
	HD	5,504,035	04/02/96	Rostoker et al.			
	HE	5,504,183	04/02/96	Shi			
	HF	5,511,238	04/23/96	Bayraktaroglu			
	HG	5,512,773	04/96	Wolf et al.			
	нн	5,515,047	05/07/96	Yamakido et al.			
	н	5,515,810	05/14/96	Yamashita et al.			
	HJ	5,519,235	05/96	Ramesh	i i		
	нк	5,549,977	08/96	Jin et al.			
	HL	5,551,238	09/03/96	Prueitt			
	нм	5,552,547	09/03/96	Shi			
	HN	5,589,284	12/31/96	Summerfelt et al.			
	НО	5,602,418	02/11/97	lmai et al.			
	HP	5,633,724	05/27/97	King et al.			

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INITIAL	IA	NUMBER 5,650,646	07/22/97	Summerfelt		CLASS	IF APPROPRIATE
	IB	5,656,382	08/12/97	Nashimoto		-	
	IC IC	5,659,180	08/19/97	Shen et al.		-	
	ID	5,661,112	08/26/97	Hatta et al.			
	IE	5,679,965	11/95	Schetzina			
	IF	5,725,641	03/10/98	MacLeod			
	IG	5,745,631	04/28/98	Reinker		-	
	IH	and the second s	07/07/98	Nashimoto			-
	iii	5,776,621 5,777,350	07/07/98	Nakamura et al.			
	IJ	5,789,845	08/04/98	Wadaka et al.		 	
	IK	5,792,569	08/11/98	Sun et al.		 	<u> </u>
	IL	5,792,679	08/11/98	Nakato		 	
	IM	5,796,648	08/18/98	Kawakubo et al.			
	IN	5,801,072	09/01/98	Barber		1	
	10	5,812,272	09/22/98	King et al.			
	IP	5,814,583	09/98	Itozaki et al.	-		
	IQ	5,825,055	10/20/98	Summerfelt		 	
	IR	5,827,755	10/27/98	Yonchara et al.			
	is	5,833,603	11/10/98	Kovacs et al.		 	
	IT	5,838,035	11/17/98	Ramesh			
	IU	5,844,260	12/01/98	Ohori			
-	IV	5,846,846	12/08/98	Suh et al.		1	
	iw	5,863,326	01/26/99	Nause et al.		+ +	
	IX	5,872,493	02/16/99	Ella			
	ı^ ıY	5,879,956	03/99	Seon et al.		 	
	ız	5,880,452	03/09/99	Plesko			· · · · · · · · · · · · · · · · · · ·
-	JA	5,883,564	03/16/99	Partin	-		
	JB	5,907,792	05/25/99	Droopad et al.			
	nc PB	5,937,274	08/10/99	Kondow et al.		+	
	ND DC	5,948,161	09/07/99	Kizuki			
-	JE	5,959,879	09/28/99	Koo		+	
	JF	5,966,323	10/99	Chen et al.			
	JG	5,987,011	11/16/99	Toh		 	
	NH PG	6,022,140	02/08/00	Fraden et al.		 	-
	JI	6,022,410	02/08/00	Yu et al.		-	
	77	6,023,082	02/08/00	McKee et al.			
· · · · ·	JK	6,028,853	02/22/00	Haartsen			
	JL	6,049,702	04/11/00	Tham et al.			
	JM JE	6,078,717	06/20/00	Nashimoto et al		 	
	JN	6,088,216	07/00	Laibowitz et al.		 	_
<u></u>	10	6,090,659	07/00	Laibowitz et al.		+ -+	
	JP	6,107,721	08/22/00	Lakin			
	JQ	6,153,010	11/28/00	Kiyoku et al		-	

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				APPLICANT			
LIST OF REFERENCES CITED BY APPLICANT			Jamal RAMDANI,		, et al. I GROUP		
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INITIAL		NUMBER			02.00	CLASS	IF APPROPRIATE
	MA	5,553,089	09/03/96	Seki et al.			
	МВ	5,528,057	06/18/96	Yanagase et al.			
	МС	6,229,159	05/08/01	Suzuki			
	MD	4,748,485	05/31/88	Vasudev			
	ME	4,984,043	01/08/91	Vinal			
	MF	5,754,319	05/19/98	Van De Voorde et al.			
	MG	6,108,125	08/22/00	Yano			
	МН	5,073,981	12/17/91	Giles et al.			
	MI	5,140,651	08/18/92	Soref et al.			
	MJ	5,610,744	03/11/97	-Ho et al.			
	MK	6,362,017	03/26/02	Manabe et al.			·
	ML	6,242,686	06/05/01	Kishimoto et al.			
	ММ	5,689,123	11/18/97	Major et al.			
	MN	5,670,800	09/23/97	Nakao et al.			
	МО	5,067,809	11/26/91	Tsubota			
	MP	5,596,205	01/21/97	Reedy et al.			
	MQ	6,175,555	01/16/01	Hoole			
	MR	5 ,357,122	10/18/94	Okubora et al.			* .
	MS	4,084,130	04/11/78	Holton			
	МТ	6,093,302	07/25/00	Montgomery			
1	MU	6,372,813	04/16/02	Johnson et al.			
	MV	5,608,046	03/04/97	Cook et al.			
	MW	5,955,591	09/21/99	Imbach et al.			
	МХ	6,022,963	02/08/00	McGall et al.			
	MY	6,083,697	07/04/00	Beecher et al.			
_	MZ	5,063,081	11/05/91	Cozzette et al.			
	NA	5,479,317	12/26/95	Ramesh			
	NB	5,306,649	04/26/94	Hebert			
_	NC	5,962,069	10/05/99	Schindler et al.			
	ND	5,541,422	07/30/96	Wolf et al.			
	NE	5,873,977	02/23/99	Desu et al.	-		
	NF	5,538,941	07/23/96	Findikoglu et al.			•
	NG	6,046,464	04/04/00	Schetzina			
	NH	6,235,145	05/22/01	Li et al.			
	NI	5,610,744	03/11/97	Ho et al.			
	NJ	5,280,013	01/18/94	Newman et al.			
	NK	6,348,373 B1	02/19/02	Ma et al.	_		
	NL	6,339,664 B1	01/15/02	Farjady et al.		-	
	NM	4,439,014	03/27/84	Stacy et al.			
	NN	4,889,402	12/26/89	Reinhart			
	NO	5,963,291	10/05/99	Wu et al.			-
	NP	6,011,641	01/04/00	Shin et al.			
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	OA	5,807,440	09/15/98	Kubota et al.			
	ОВ	4,681,982	07/21/87	Yoshida			
	ОС	4,629,821	12/16/86	Bronstein-Bonte et al.			
	OD	4,452,720	06/05/84	Harada et al.			
	OE	3,935,031	01/27/76	Adler			
	OF	5,760,426	06/02/98	Marx et al.			
	OG	5,053,835	10/01/91	Horikawa et al.			
	ОН	6,326,645 B1	12/04/01	Kadota			
	01	5,770,887	06/23/98	Tadatomo et al.			
	Ol	6,372,356 B1	04/16/02	Thornton et al.			
	ОК	4,774,205	09/27/88	Choi et al.			
	OL	6,359,330 B1	03/19/02	Goudard			
	ОМ	5,312,765	05/17/94	Kanber			
	ON	5,734,672	03/31/98	McMinn et al.			
	00	6,367,699 B2	04/09/02	Ackley			
	OP	5,530,235	06/25/96	Stefik et al.	<u>.</u>		
	OQ	5,623,552	04/22/97	Lane			
	OR	5,481,102	01/02/96	Hazelrigg, Jr.			
	os	6,134,114	10/17/00	Ungermann et al.			
	от	5,984,190	11/16/99	Nevill			
	ου	5,789,733	08/04/98	Jachimowicz et al.			
	ΟV	5,753,300	05/19/98	Wessels et al.			
	ow	6,208,453	03/27/01	Wessels et al.			
	ОХ	5,886,867	03/23/99	Chivukula et al.			
	OY	5,028,976	07/02/91	Ozaki et al.			
	oz	5,869,845	02/09/99	Vander Wagt et al.			
	PA	5,596,214	01/21/97	Endo			
	РВ	6,391,674 B2	05/21/02	Ziegler			
	РС	6,275,122 B1	08/14/01	Speidell et al.			
	PD	6,238,946 B1	05/29/01	Ziegler			
	PE	6,210,988 B1	04/03/01	Howe et al.			
	PF	6,392,257	05/21/02	Ramdani et al.			
	PG	4,442,590	04/17/84	Stockton et al.			
	PH	5,603,764	02/18/97	Matsuda et al.			
	PI	6,087,681	06/11/00	Shakuda	<u> </u>		
	PJ	5,132,648	07/21/92	Trinh et al.	<u> </u>		
	PK	6,427,066	07/30/02	Grube	<u> </u>		.
	PL	2002/0072245	06/13/02	Ooms et al.	<u> </u>		
	РМ	6,278,138 B1	08/21/01	Suzuki	ļ		
	PN	5,888,296	03/30/99	Ooms et al.	<u> </u>		
	РО	5,198,269	03/3093	Swartz et al.			
	PP	2002/0030246	03/14/02	Eisenbeiser et al.	 		
	PQ	2002/0047143	04/25/02	Ramdani et al.			

Form PTO 1449 U.S. DEPARTMENT OF COMMERCE		ATTY DOCKET NO.		SERIAL NO				
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	QA	5,776,359	07/07/98	Schultz et al.				
	QB	5,569,953	10/29/96	Kikkawa et al.				
	QC	5,834,362	11/10/98	Miyagaki et al.				
	QD	6,248,621 B1	06/19/01	Wilk et al.				
	QE	5,266,355	11/30/93	Wernberg et al.				
	QF	6,277,436 B1	08/21/01	Stauf et al.				
	QG	6,039,803	03/21/00	Fitzgerald et al.				
	QH	5,619,051	04/08/97	Endo				
	QI	5,420,102	05/30/95	Harshavardhan et al.				
-	۵ı	5,210,763	05/11/93	Lewis et al.				
	QK	5,103,494	04/07/92	Mozer				
	QL	4,594,000	06/10/86	Falk et al.				
	QM	4,297,656	10/27/81	Pan				
	QN	5,244,818	09/14/93	Jokers et al.				
	QO	6,048,751	04/11/00	D'Asaro et al.				
	QP	5,484,664	01/16/96	Kitahara et al.	81. 10			
	QQ	5,780,311	07/14/98	Beasom et al.				
	QR	6,438,281 B1	08/20/02	Tsukamoto et al.				
	QS	5,399,898	03/21/95	Rostoker				
	QT	6,271,619	08/07/01	Yamada et al.				
	QU	5,334,556	08/02/94	Guldi				
	QV	4,910,164	03/20/90	Shichijo				
	QW	4,952,420	08/28/90	Walters				
	QX	6,121,647	09/19/00	Yano et al.				
	QY	6,306,668 B1 ´	10/23/01	McKee et al.		-		
	QZ	6,143,366	11/07/00	Lu				
	RA	6,410,941	06/25/02	Taylor et al.				
	RB	5,397,428	03/14/95	Stoner et al.	-			
	RC	6,432,546 B1	08/13/02	Ramesh et al.				
	RD	6,345,424	02/12/02	Hasegawa et al.				
	RE	6,338,756 B2	01/15/02	Dietze				
	RF	5,516,725	05/14/96	Chang et al.				
	RG	4,667,212	05/19/87	Nakamura				
	RH	5,629,534	05/13/97	Inuzuka et al.				
	RI	3,914,137	10/21/75	Huffman et al.				
	RJ	5,753,928	05/19/98	Krause				
	RK	5,977,567	11/02/99	Verdiell				
	RL	5,130,762	07/14/92	Kulick			<u> · </u>	
	RM	5,621,227	04/15/97	Joshi	_			
	RN	6,389,209 B1	05/14/02	Suhir				
	RO	5,163,118	11/10/92	Lorenzo et al.			· -	
	RP	5,926,493	07/20/99	O'Brien et al.				
	RQ	5,323,023	06/21/94	Fork				

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	SA	6,156,581	12/05/00	Vaudo et al.			
	SB	5,395,663	03/07/95	Tabata et al.			
	SC	4,146,297	03/27/79	Alferness et al.			
	SD	5,452,118	09/19/95	Maruska			
	SE	5,889,296	03/30/99	Imamura et al.			
	SF	6,300,615 B1	10/09/01	Shinohara et al.			
	SG	6,232,910 B1	05/15/01	Bell et al.			
	SH	5,686,741	11/11/97	Ohori et al.			
	SI	4,959,702	09/25/90	Moyer et al			
	SJ	6,100,578	08/08/00	Suzuki			
	SK	6,410,947 B1	06/25/02	Wada			
	SL	6,417,059 B2	07/09/02	Huang	i		
	SM	6,461,927 B1	10/08/02	Mochizuki et al.			
	SN	6,462,360 B1	10/08/02	Higgins, Jr. et al.			
	so	5,981,976	11/09/99	Murasato	<u> </u>		
	SP	5,981,980	11/09/99	Miyajima et al.			
	SQ	2002/0006245 A1	01/17/02	Kubota et al.			
	SR	2002/0131675 A1	09/19/02	Litvin			
<u> </u>	SS	6,256,426 B1	07/03/01	Duchet			
	ST	6,278,523 B1	08/21/01	Gorecki			
	SU	6,319,730 B1	11/20/01	Ramdani et al.		-	
-	sv	6,404,027	06/11/02	Hong et al.			
	sw	6,312,819 B1	11/06/01	Jia et al.			
	SX	5,119,448	06/02/92	Schaefer et al.			
	SY	4,120,588	10/17/78	Chaum			
	SZ	5,194,917	03/16/93	Regener			
	TA	5,018,816	05/28/91	Murray et al.			
	тв	5,953,468	09/14/99	Finnila et al.			
	TC	5,561,305	10/01/96	Smith	<u> </u>		
	TD	5,896,476	04/20/99	Wisseman et al.			
	TE	4,934,777	06/19/90	Jou et al.			
	TF	6,320,238 B1	11/20/01	Kizilyalli et al.			
	TG	6,393,167 B1	05/21/02	Davis et al.			
	тн	5,760,427	06/02/98	Onda			
	TI	6,411,756 B2	06/25/02	Sadot et al.	-		
	TJ	5,668,048	09/16/97	Kondo et al.			
	TK	5,852,687	12/22/98	Wickham			
	TL	5,122,852	06/16/92	Chan et al.			
	ТМ	5,173,835	12/22/92	Cornett et al.			
	TN	5,055,835	10/08/91	Sutton			
	то	6,139,483	10/31/00	Seabaugh et al.			
	TP	5,283,462	02/01/94	Stengel			
	TQ	6,103,403	08/15/00	Grigorian et al.	<u> </u>		
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	<u> </u>	55-87424		Japan w/English Abstract	x	
		61-108187	05/26/86	Japan w/English Abstract	r x	
	AAS	6-232126	08/19/94	Japan	<u> </u>	
***	AAT	6-291299	10/18/94	Japan w/English Abstract	<u>x</u>	
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	AAV	63-131104	<u> </u>	Japan w/English Abstract	X	
	1	63-198365	08/17/88		<u>^</u>	
		10-321943	12/04/98	Japan	x	
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	ABC	WO 99/19546	04/22/99	WIPO WIPO		
	ABD	WO 00/33363 WO 00/48239	08/17/00	WIPO	ļ	ļ
	ABF	WO 99/14797	03/25/99	WIPO Great Britain		
	ABG	GB 2 335 792		Europe Europe		<u> </u>
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	ABI		10/30/97	Japan w/English Abstract		<u> </u>
	ABJ	60-212018	10/24/85	Japan w/English Abstract		
		60-210018 WO 92/10875	06/25/92	WIPO	ļ	
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	ABM	0 682 266	11/15/95	Europe	-	
	ABN	3-41783	02/91	Japan (English Abstract only)		
		0 581 239	02/02/94	Europe		
	ABP	0812494	01/16/96	Japan		
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	BAA	1 043 426	10/11/00	Europe		
	BAB	2000-068466	03/00	Japan (Abstract)		
	BAC	64-50575	02/27/89	Japan		
	BAD	WO 98/05807	01/12/98	WIPO		
	BAE	WO 94/03908	02/17/94	WIPO		
	BAF	WO 01/33585	05/10/01	WIPO		
	BAG	1-102435	04/20/89	Japan w/English Abstract		
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	BAI	02051220	02/21/90	Japan (English Abstract)		
	BAJ	11135614	05/21/99	Japan (w/English Abstract)		
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	BAN	10-303396	11/13/98	Japan (w/English Abstract)		
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	BAP	0 964 259	12/15/99	Europe		
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		61-63015	04/01/86	Japan w/English Abstract	 	
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		0 964 453	12/15/99	Europe		
	BAY	5-152529	06/18/93	Japan w/English Abstract		
	BAZ	9-67193	03/11/97	Japan w/English Abstract		
	BBA	9-82913	03/28/97	Japan w/English Abstract		
		0 309 270	03/29/89	Europe		
	BBC	EP 0 957 522	11/17/99	Europe		
	BBD	EP 0 810 666	12/03/97	Europe		
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	BBF	DE 100 17 137	10/26/00	GERMANY		
	BBG	WO 02 01648	01/03/02	WIPO		
	BBH	WO 02/33385 A2	04/25/02	WIPO		
	BBI	WO 02/53365 A2	08/16/01	WIPO		
		WO 01/59814 A2 WO 02/09160 A2	01/31/02	WIPO		
	BBJ	WO 02/09160 A2 WO 00/06812	02/10/00	WIPO		
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		0 538 611	04/28/93	Europe		
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		05150143	06/18/93	Japan (English Abstract only)		
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		WO 02/03467	01/10/02	WIPO		
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		61-36981	02/21/86	Japan w/English Abstract		
		WO 93/07647		WIPO		
	CAH	2002-9366	01/11/02	Japan w/English Abstract		
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	CAU	EP 1 085 319	03/21/01	Europe	.,	
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	CAW	2000-351692	12/19/00	Japan w/English Abstract		
	CAX	03-188619	08/16/91	Japan (English Abstract only)		
	CAY	63-289812	11/28/88	Japan (English Abstract only)		
	CAZ	EP 0 884 767	12/16/98	Europe		
	CBA	06-069490	03/11/94	Japan (English Abstract only)		
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Form PTO 1449	U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE	ATTY DOCKET NO.	SERIAL NO.					
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				FILING DATE		GROUP	
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